US00D959393S

(12) **United States Design Patent**
Sugiura et al.

(10) **Patent No.: US D959,393 S**
(45) **Date of Patent: ** Aug. 2, 2022**

(54) **CEILING HEATER FOR SUBSTRATE PROCESSING APPARATUS**

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(**) Term: **15 Years**

(21) Appl. No.: **29/773,979**

(22) Filed: **Mar. 12, 2021**

(30) **Foreign Application Priority Data**

Sep. 24, 2020 (JP) .... 2020020257 D

(51) **LOC (13) Cl.** **13-03**

(52) **U.S. Cl.**
USPC **D13/182**

(58) **Field of Classification Search**
USPC D13/184, 182; D15/144, 144.1, 144.2, D15/146, 140; D23/314, 322, 333, 415, D23/417, 499
CPC H01L 21/67115; H01L 21/67098; H01L 21/67103; C23C 16/455; C23C 16/46
See application file for complete search history.

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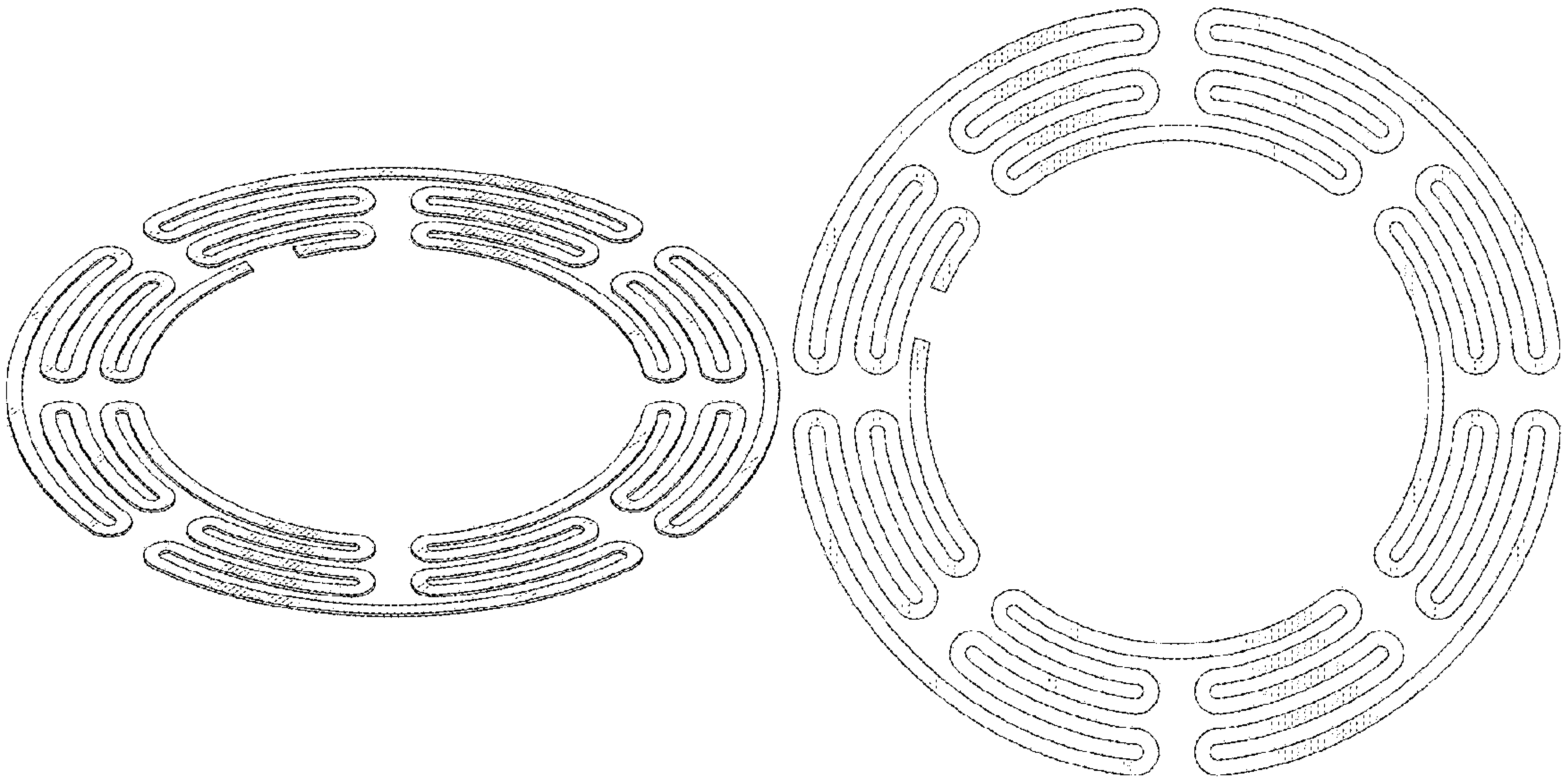
(57) **CLAIM**

The ornamental design for a ceiling heater for substrate processing apparatus, as shown and described.

DESCRIPTION

FIG. **1** is a front, top and right side perspective view of a ceiling heater for substrate processing apparatus showing our new design;
FIG. **2** is a front elevational view thereof;
FIG. **3** is a left side elevational view thereof;
FIG. **4** is a right side elevational view thereof;
FIG. **5** is a top plan view thereof;
FIG. **6** is a bottom plan view thereof; and,
FIG. **7** is a rear elevational view.

1 Claim, 4 Drawing Sheets



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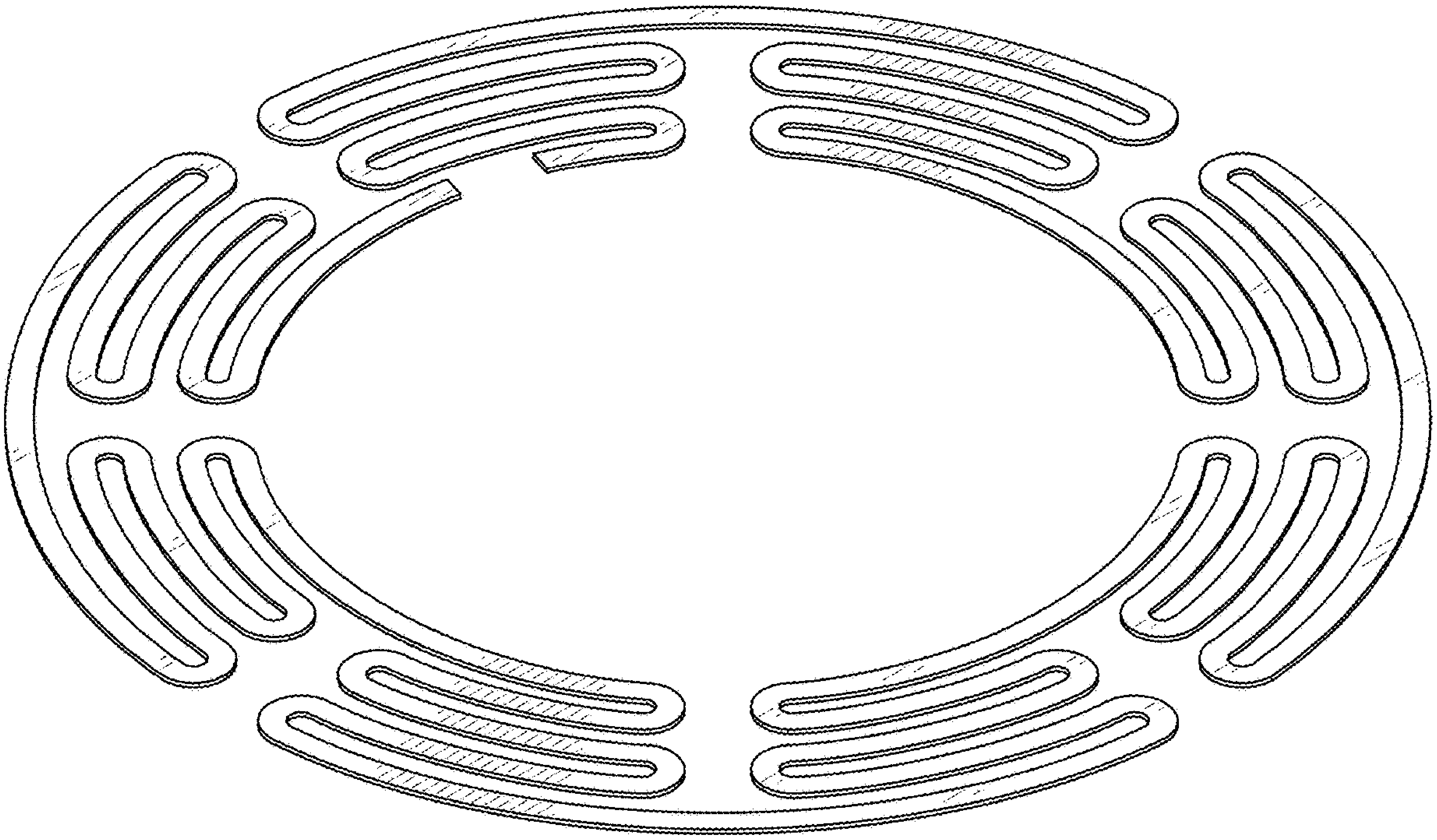

FIG. 1

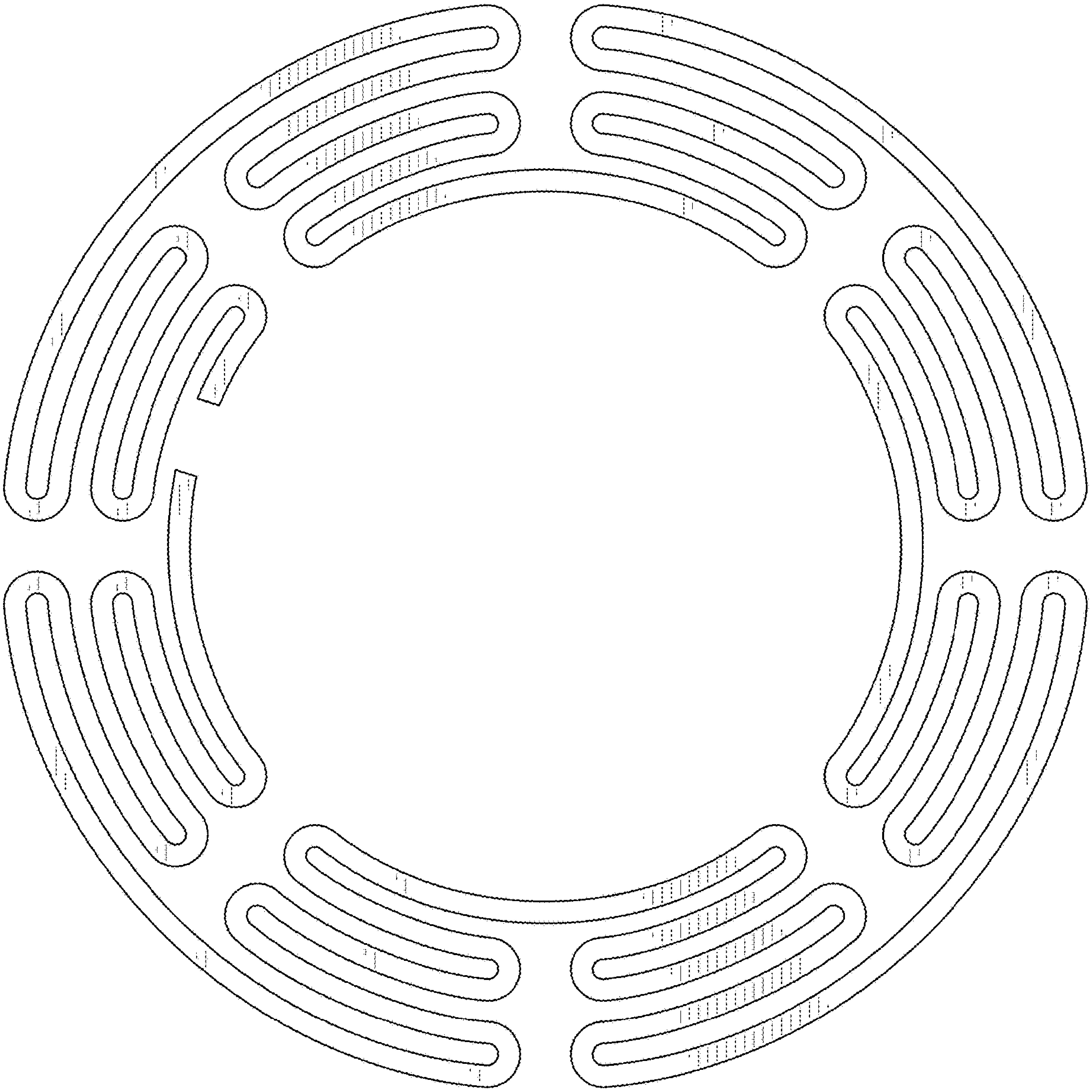

FIG. 2

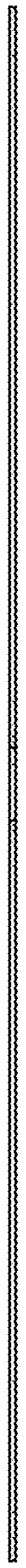

FIG. 3

FIG. 4

FIG. 5

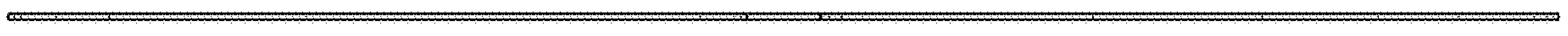

FIG. 6

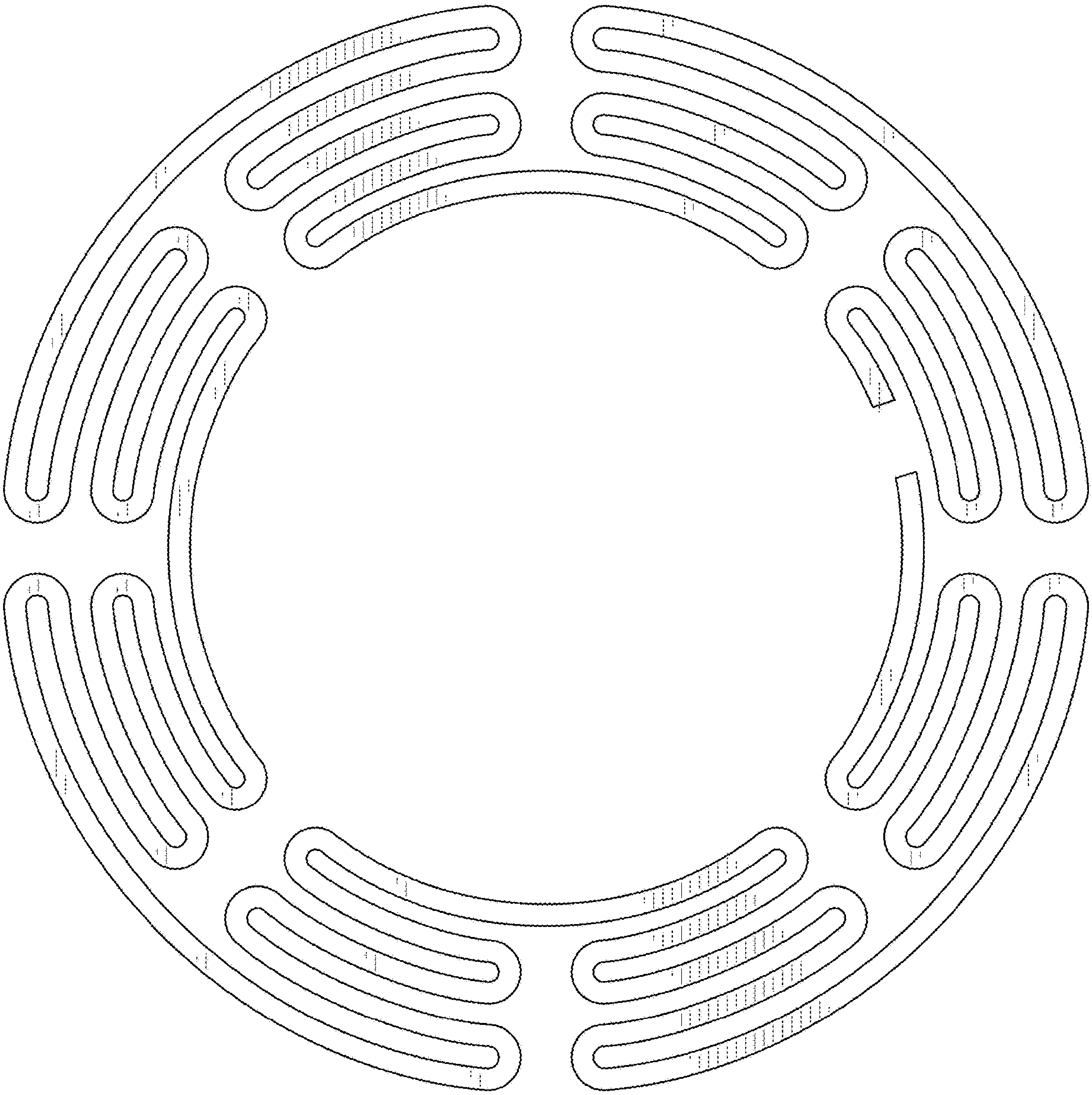

FIG. 7